

L Number	Hits	Search Text	DB	Time stamp
1	73	(((reactive adj ion adj etch\$.ti.) or ((dry adj etch\$4).ti.)) and ((helium or he) and ((sulfur adj hexaflu\$6) or ("SF.sub.6") or (sf6)) and (o2 or oxygen))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 14:23
-	42	"4943719"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:01
-	51	"5021364"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:01
-	100	"5475318"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:01
-	24	"5489774"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:01
-	5	"5856964"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:27
-	0	Il-Choo	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:01
-	1767	choo.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:02
-	7	Il-Joo.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:03
-	152	probe and cantilever and mask and silicon and (boron or boron-diffus\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	39552	cho.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:04
-	1	09/598,656	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:04

-	1	09/598656	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:05
-	3922	probe same cantilever	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:12
-	284	(probe same cantilever) and ("SiO.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:12
-	248	(probe same cantilever) and (silicon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:12
-	95	((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:13
-	28	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:13
-	20	((probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))) and "<110>"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:13
-	0	(((((probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))) and "<110>") and (reactive adj ion)) and He	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:13
-	3	(((((probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))) and "<110>") and (reactive adj ion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:17
-	781	(reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 11:25
-	1	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and ((reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:20
-	10	((reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))) and probe and cantilever	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:20

-	44	"4968585"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:23
-	235	"4943719" or "4968585" or "5021364" or "5475318" or "5489774" or "5856964"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:23
-	5	("4943719" or "4968585" or "5021364" or "5475318" or "5489774" or "5856964") and ((reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:23
-	200	probe and cantilever and mask and silicon and (boron or boron-diffus\$4 or (p adj type) or "p-type" or (p adj doped))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 08:28
-	14	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4 or (p adj type) or "p-type" or (p adj doped))) and ("110" same crystal same substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:01
-	26	("4382228" "4480223" "4585991" "4599559" "4719417" "4961052" "5172050" "5177438" "5177439" "5475318" "5521518" "5723347" "5869974" "5900738" "5903161" "5923952" "5926029" "5929498" "5959957" "5965943" "6037785" "6064217" "6072190" "6146917" "6246245" "6279227").PN.	USPAT	2004/10/05 08:54
-	200	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4 or (p adj type) or "p-type" or (p adj doped)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:02
-	9	"5856967"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:28
-	24	"5489774"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:28
-	51	"5021364"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:32
-	1193	((((reactive adj ion) or (dry adj etch\$4)) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:35
-	4	(((((reactive adj ion) or (dry adj etch\$4)) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6")))) and probe and cantilever and mask and layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:35

-	104385	silicon adj dioxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:44
-	329074	silicon same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:45
-	313759	(silicon same (wafer or substrate)) and probe and cantilever and body and tip and "p type" or p-type or boron	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:46
-	113	(silicon same (wafer or substrate)) and probe and cantilever and body and tip and ("p type" or p-type or boron)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 09:48
-	48	((silicon same (wafer or substrate)) and probe and cantilever and body and tip and ("p type" or p-type or boron)) and "110"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:04
-	84	cantilever and probe and tip and (silicon adj dioxide) and doped and mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:04
-	21	cantilever and probe and tip and (silicon adj dioxide) and doped and (dry adj etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:12
-	2773	cantilever and probe and tip	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:12
-	566	(cantilever and probe and tip) and 250/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:13
-	47	(cantilever and probe and tip) and dop\$3 and ((dry adj etch\$4) or (reactive adj ion adj etch\$4) or RIE) and (silicon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:14
-	15	((cantilever and probe and tip) and 250/\$.ccls.) and dop\$3 and ((dry adj etch\$4) or (reactive adj ion adj etch\$4) or RIE) and (silicon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:19
-	583	tip and cantilever and (silicon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 10:19
-	36	4968585.URPN.	USPAT	2004/10/05 10:48
-	40	5021364.URPN.	USPAT	2004/10/05 10:54

-	19	(reactive adj ion) and ((he or helium) and (o2 or "o.sub.2")) and ((sulfur adj hexaf\$6) or "SF.sub.6")) and cantilever and layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 11:26
-	1322	((reactive adj ion) or (dry adj etch\$4)) and cantilever and layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 11:28
-	634	((((reactive adj ion) or (dry adj etch\$4)) and cantilever and layer) and "110"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 11:28
-	1322	((reactive adj ion) or (dry adj etch\$4))and cantilever and layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 11:28
-	634	((((reactive adj ion) or (dry adj etch\$4)) and cantilever and layer) and "(110)"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:46
-	0	216/11.216/2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:46
-	1859	216/2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	637	148/33.3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	3166	250/306	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	2443	250/307	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	712	324/719	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	725	324/750	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47

-	5359	324/754	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	1966	73/105	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	11	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 216/2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:48
-	1	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 148/33.3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	53	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/306	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:47
-	37	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:48
-	37	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:48
-	3	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/719	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:48
-	2	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/750	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:48
-	20	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/754	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:48

-	78	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 216/2) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 148/33.3) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/306) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/719) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/750) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/754)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 13:56
-	10	5026437.URPN.	USPAT	2004/10/05 13:49
-	44	((probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 216/2) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 148/33.3) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/306) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/719) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/750) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/754)) and "1,1,0"	USPAT; USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 14:02
-	1444	(reactive adj ion adj etch\$.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 14:04
-	1	((reactive adj ion adj etch\$.ti.) and he and (o2 or o.sub\$4) and (sulfur adj hexaflu\$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 14:06
-	0	((reactive adj ion adj etch\$.ti.) and he and sf6 and o2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/05 14:06